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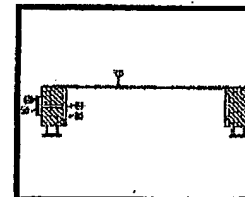
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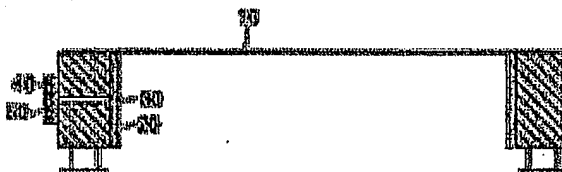
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**Derwent Title:** Pellicle filter structure for photo mask  
**Assignee:** HYNIX SEMICONDUCTOR INC Non-standard company  
**Inventor:** WON J I;  
**Accession/Update:** 2004-363005 / 200434  
**IPC Code:** H01L 21/027 ;  
**Derwent Classes:** U11;  
**Manual Codes:** U11-C04D(Masking techniques for microlithography) , U11-C04E1(Apparatus and method for photolithography)



**Derwent Abstract:** (KR4001785A) **Novelty** - A pellicle filter structure for a photo mask is provided to be capable of preventing the contamination due to chemicals by installing a chemical filter at the outer surface of an air filter.

**Detailed Description** - A pellicle filter structure for a photo mask is provided with a pellicle(10) made of transparent film capable of transmitting light, a frame(20) for supporting the lower portion of the pellicle, a vent hole(30) formed at the inner portion of the frame for flowing air, and an air filter(40) installed at the outer surface of the frame for blocking the vent hole in order to filter foreign substance. The pellicle filter structure further includes a chemical filter(50) installed at the outer surface of the air filter for preventing chemicals from being flowed into the vent hole.

**Images:**

Dwg.1/10

**Family:** PDF Patent Pub. Date Derwent Update Pages Language IPC Code  
 KR4001785A \* 2004-01-07 200434 1 English H01L 21/027  
 Local appls.: KR2002000037107 Filed:2002-06-28\*(2002KR-0037107)

**Priority Number:**

Application Number	Filed	Original Title
KR2002000037107	2002-06-28	

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## KOREAN PATENT ABSTRACTS

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(21)Application number:	<b>1020020037107</b>	(71)Applicant:	<b>HYNIX SEMICONDUCTOR INC.</b>
(22)Date of filing:	<b>28.06.2002</b>	(72)Inventor:	<b>WON, JUN IL</b>
(51)Int. Cl.	<b>H01L 21/027</b>		

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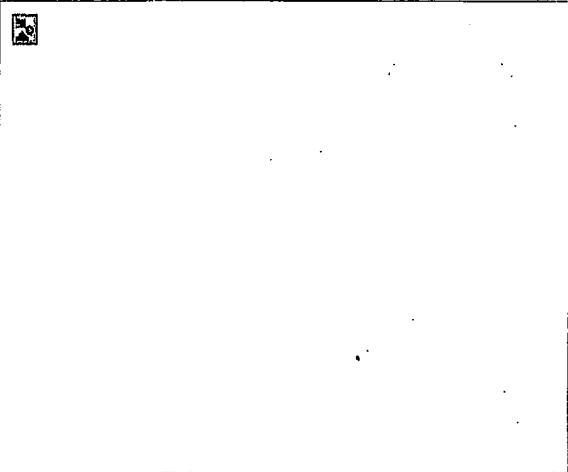
## (54) PELLICLE FILTER STRUCTURE FOR PHOTO MASK

## (57) Abstract:

PURPOSE: A pellicle filter structure for a photo mask is provided to be capable of preventing the contamination due to chemicals by installing a chemical filter at the outer surface of an air filter.

CONSTITUTION: A pellicle filter structure for a photo mask is provided with a pellicle(10) made of transparent film capable of transmitting light, a frame(20) for supporting the lower portion of the pellicle, a vent hole(30) formed at the inner portion of the frame for flowing air, and an air filter(40)

installed at the outer surface of the frame for blocking the vent hole in order to filter foreign substance. The pellicle filter structure further includes a chemical filter(50) installed at the outer surface of the air filter for preventing chemicals from being flowed into the vent hole.



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